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Department of Homeland Security
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Ref: Dr. Clement Riedel's contributions to Applied Physics Letters as an author and reviewer

To Whom It May Concern:

As the Editor-in-Chief of *Applied Physics Letters*, I am writing this letter to confirm that **Dr. Clement Riedel** (University of California in Berkeley, QB3 Institute, Berkeley, CA 94703) has published two scientific papers in, and reviewed one manuscript submitted to, this Journal since 2010. His research expertise is in the areas of Dielectrics, Atomic Force Microscopy, Nanostructure, and Subsurface Characterization.

Applied Physics Letters is a weekly scientific journal published by AIP Publishing LLC (American Institute of Physics), Suite 1NO1, 2 Huntington Quadrangle, Melville, NY 11747. It offers prompt publication of new experimental and theoretical papers bearing on applications of physics to all branches of science, engineering, and modern technology. Submitted manuscripts undergo a stringent peer-review process to assure high quality as well as scientific and/or technical relevance. Papers accepted for *Applied Physics Letters* are considered important and warrant rapid publication due to their potential applications and/or impact on the work of other researchers in the same field. In recent years, only about 40% of submitted manuscripts were accepted for publication.

The task of peer review is of fundamental importance to the publication and dissemination of scientific results. To evaluate new submissions and to maintain the high quality of our publications, we rely on the advice of expert reviewers, established as knowledgeable and competent in their fields, who perform this duty on a volunteer basis beyond their regular professional obligations as a service to the Journal and to the scientific community. We consider our Reviewer Database to be an extremely valuable tool for identifying the most appropriate individuals as referees for each manuscript. Our selection criteria include their international reputation, subject area expertise, quality of previous contributions, and maturity to fairly judge the work of colleagues. The participation of dedicated reviewers in evaluating the significance and appropriateness

of manuscripts is, to a major extent, responsible for the preeminent standing of *Applied Physics Letters* among international research journals on applied physics. We appreciate Dr. Riedel's contribution and look forward to his future assistance.

Applied Physics Letters is the most-highly-cited international journal in the field of applied physics, with 212,433 citations to the Journal made from all journals published worldwide in 2012. The Journal's 2012 impact factor and EigenFactor score are 3.794 and 0.5882, respectively. Criteria for assessing the relevance of a journal are often based on the number of citations made each year to articles published in the journal. The most widely accepted data come from Thomson Reuters (formerly the Institute for Scientific Information, ISI), which annually release citation statistics products. *Applied Physics Letters* is consistently ranked first among the 127 journals in the Thomson Reuters' subject category of applied physics in terms of total citations. In addition, according to the recent *Journal Popularity Report* (ExLibris bX, Q4 2013), *Applied Physics Letters* stands in the top 50 of the world's 50,000 most-used journals. It is indeed a well-read journal, boasting nearly 5 millions of full-text article downloads per year over the past several years. This clearly demonstrates the importance of *Applied Physics Letters*, particularly given the high relevance of the field of applied physics.

The widespread distribution and international character of *Applied Physics Letters* can be gauged by the fact that 12,231 manuscripts were submitted for publication from some 80 countries in 2013. Additional information about the Journal can be obtained from our website (<http://apl.aip.org>).

Sincerely,

A handwritten signature in black ink, appearing to read 'Nghi Q. Lam', with a long horizontal flourish extending to the right.

Nghi Q. Lam, Ph.D.
Editor-in-Chief

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